Influences of Solution Plasma Conditions on Degradation Rate and

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2	Properties of Chitosan
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Abstract

In this work, the effects of solution plasma conditions on the degradation rate and properties of chitosan are investigated. Various types of electrodes including tungsten (W), copper (Cu), and iron (Fe) were used. The treatment time and the applied pulse frequency of the bipolar supply varied from 0 to 210 minutes and 15 to 30 kHz, respectively. The plasma-treated chitosan was characterized by GPC, XRD, FT-IR, and fractionation analysis. The results showed that after plasma treatment for 210 minutes, the molecular weight of chitosan decreased remarkably, when compared to those of untreated samples. The plasma treatment of chitosan using Fe electrode and high pulse frequency strongly promoted the degradation rate of chitosan. The XRD analysis showed that the crystallinity of plasma-treated chitosan was destroyed. FT-IR analysis revealed that the chemical structure of chitosan was not changed by solution plasma treatment. Solution plasma treatment of chitosan using an Fe electrode provided the highest %yield of water-soluble chitosan.

Keywords

42 Solution Plasma Process; Chitosan; Degradation rate

1. Introduction

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Chitosan, the deacetylated derivative of chitin, is one of the abundant, nontoxic, renewable, biodegradable polymers. It is composed of β-1,4-linked 2amino-2-deoxy-D-glucopyranose (GlcN) and 2-acet-amido-2-deoxy-D-glucopyranose (GlcNAc) units and widely presented in exoskelatons of shellfish and insect (Shahidi et al., 1999; Jayakumar et al., 2010; Jayakumar et al., 2011). Therefore, chitosan has received much attention for various applications such as food, pharmaceutics, biomaterials, drug delivery, medicine and cosmetics. However, the high molecular weight, high viscosity, and low solubility in water of chitosan derived from chitin are the main problems and restrict its application. Several techniques including chemical, physical and enzymatic treatment have already been performed to degrade the high molecular weight chitosan into low molecular weight chitosan (LMWC) which exhibits water solubility, bioactivities including antitumor, antimicrobial as well as anti-inflammatory properties (Yue et al., 2008; Xie et al., 2009; Choi et al., 2002; Chang et al., 2001). Among these techniques, enzymatic treatment is an effective process to achieve LMWC. However, the main drawbacks of this process are low production yield and slowly enzymatic reaction. In addition, since it is operated under mild conditions and requires multiple steps, especially enzyme preparation and product purification, therefore, this process is considered as the complicated and high cost process. Electrical discharge in the liquid phase is known as "Solution plasma process (SPP)", and has recently been proposed to be an effective process. Currently, SPP has received much attention for various applications such as carbon material synthesis, surface modification of polymers, wastewater treatment, and degradation of organic compounds (Takai, 2008). An important advantages of SPP is the production of

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highly active species especially hydroxyl radicals (OH') is obtained (Potocký et al., 2009; Prasertsung et al., 2011; Prasertsung et al., 2013). Moreover, since the solution plasma is generated under mild conditions and not involved any strong chemical reagents, therefore the removal of chemical residue is not required. The present study was aimed to study the effects of SPP conditions on the degradation rate and properties of the degraded chitosan product. For this purpose, the degradation of β-chitosan was carried out by SPP with different types of electrodes and the applied pulse frequency. The degradation rate of chitosan was calculated by kinetic study. The properties of chitosan including the molecular weight, chemical structure, crystal structure and solubility were investigated. The properties of degraded products were characterized by GPC, FT-IR, and XRD. Moreover, the water solubility of degraded product was then determined by fractional analysis.

2. Materials and Methods

2.1 Materials

β-Chitosan was prepared according to a procedure similar to that described by Sashiwa *et al.* (Sashiwa et al., 2003). In short, the ground squid pen was soaked in 2 N NaOH solution overnight to deproteinize. The deproteinized product were then treated with a similar solution at 100° C for 4 h followed by excessive washing with distilled water to remove more residual protein. The β-chitin samples were deacetylated with 25% NaOH (112.5°C) to achieve β-Chitosan with the degree of deacetylation and average molecular weight of 90% and 1.3×10^5 Da, respectively. Acetic acid, acetone, hydrochloric acid, and sodium hydroxide were used as received. All of the chemicals, reagents, and solvents used were of analytical grades. The water used was distilled and deionized.

สาเมาถูกต้อง

2.2 Solution plasma experiment

β-Chitosan was dissolved in 1 M acetic acid to obtain 0.5% w/v chitosan solution and placed in the glass reactor. The setup of solution plasma system, modified from our previous study (Prasertsung et al., 2013), is shown in Figure 1. The solution plasma was operated at atmospheric pressure. The solution plasma was produced at the fixed voltage and pulse width of 1.6 kV and 2 μs, respectively. Various types of electrodes including tungsten (W), copper (Cu) and iron (Fe) were used. The applied pulse frequency of bipolar power supply and treatment time of the solution plasma were within the ranges of 15-30 kHz and 0-210 minutes, respectively. The uniformity of chitosan solution to contact with the plasma was controlled using magnetic stirrer. After the plasma treatment of chitosan was completed, the plasma-treated and untreated chitosan were characterized.

2.3 Characterization of plasma-treated chitosan

Optical emission spectroscopy (OES) was used to monitor the light emitted from the plasma in the wavelength range of 200–1000 nm. To characterize the species in plasma-treated chitosan solutions, the emission was detected through the quartz glass window with an optical fiber placed 1 mm in front of the glass chamber. Data was acquired with Avantes software (Baroch et al., 2008).

Gel Permeation Chromatography (GPC, Water 600E, Waters, USA) was used to characterize the apparent molecular weights of plasma-treated and untreated chitosan solutions. The ultrahydrogel linear 1 column was used. The concentration of chitosan solutions was 0.4 mg/ml. Eluent and chitosan sample solutions were filtered through 0.45 μ m Millipore filters. The flow rate was maintained at 0.6 ml/min at 30°C.

The pullulans (M_w 5900-708000 Da) were used as standard samples.

สาเนาถูกห้อง

The crystal structure of both before and after degradation was characterized by X-ray diffractometer (Shimadzu Lab XRD-6000, Japan). The plasma-treated and untreated chitosan solutions were cast into mold to form thin films. X-ray diffraction patterns of the plasma-treated and untreated chitosan films were measured with a CuK α target at 40 kV and 50 mA. The relative intensity was recorded in the scattering range (2 θ) of 5-40°.

FT-IR spectroscopy (Digilab, FTS 7000 Series, USA) was used to characterize the chemical composition of plasma-treated and untreated chitosan samples. All of the ATR-FTIR spectra were collected using 64 scans in the range of 4000–400 cm⁻¹ at a resolution of 4 cm⁻¹.

2.4 Fractionation of chitosan solution

Fractionation of chitosan solution was conducted in order to determine the amount of water-soluble and water-insoluble chitosan of plasma-treated and untreated samples. In short, the pH of plasma-treated and untreated samples was adjusted to approximately 7.5 using NaOH solution. The precipitated chitosan was then removed by centrifuging at 5,000 rpm for 30 minutes. The obtained sample was coded as the first precipitate (water-insoluble chitosan). The supernatant was then mixed with an equal volume of acetone to give a second precipitate (water-soluble chitosan). The first and second precipitate chitosan samples were dried at 60°C for 24 hr. The % yields of the first and second precipitate were calculated following equation 1:

148 %yield =
$$(W_1/W_2)*100$$
 (1)



where W₁ and W₂ are the weights of dried precipitate chitosan and the chitosan added to acetic acid (untreated chitosan), respectively.

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3. Results and discussion

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3.1 The effects of types of electrodes on reactive species generated during plasma treatment

The emission spectra of plasma-treated chitosan solution, determined at a treatment time of 1 min, as a function of type of electrodes compared, are presented in Figure 2. The spectrum of the plasma-treated chitosan solution using W electrode showed strong peaks at wavelengths of 456.0, 656.5, and 777.3 nm, corresponding to H_{γ} -, H_{α} -, and O-radicals, respectively (Baroch et al., 2008). These reactive species could be generated by the decomposition of water molecules, the medium used in this study, caused by ionic current (Watthanaphanit et al., 2014). After Cu and Fe electrodes were introduced, the additional spectrum peaks were observed. In the case of Cu electrodes, the peaks were present at the wavelengths of 324.5 and 521.8 nm, corresponding to Cu I, while the Fe electrode displayed the peaks at the wavelengths of 259.9 and 425.0 nm, corresponding to Fe II (Chaves et al., 2011; Tepe et al., 1997). The presence of Cu I and Fe II species could be attributed to the erosion of copper and iron particles or ions from each electrode during solution plasma treatment. As previously reported that the erosion resistance of the Cu and Fe electrodes is relatively low compared to that of W, the release of material from electrodes was performed and sputtered by electrolysis (Potocký et al., 2009).

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3.2 The effects of type of electrodes and pulse frequency on molecular weight and degradation rate of chitosan

Table 1 shows the change in apparent molecular weight and polydispersity index (PDI) of chitosan samples during degradation by solution plasma treatment. From the GPC results, the apparent molecular weight of untreated chitosan was determined to be 1.3x10⁵ Da. After solution plasma treatment using the W electrode for 210 minutes, the molecular weight of chitosan sample was markedly decreased from the initial value to 3.1×10^4 Da. This result corresponded with our previous study and suggested that degradation of chitosan was occurred during plasma treatment. The free radicals such as hydroxyl which is performed during plasma treatment predominantly caused degradation of chitosan (Prasertsung et al., 2011; Prasertsung et al., 2013). After the Cu and Fe electrodes were employed for the degradation of chitosan by solution plasma treatment, the degradation reaction was dramatically enhanced. As shown in Table 1, the molecular weight of the degraded chitosan products was found to be 2.4x104 Da for Cu electrodes and 1.3x104 Da for Fe electrodes, respectively. Interestingly, the molecular weight of the degraded chitosan sample treated by solution plasma using Fe electrode was much lower than that of W and Cu electrodes and was considered to be low molecular weight chitosan (molecular weight in the range of 5-20 kDa) (Harish Prashanth & Tharanathan, 2007). A stronger promoting effect from the use of Fe electrodes could be attributed to the iron particle or ion, which was generated by erosion of the iron electrode via electrolysis during plasma treatment, as noted in Figure 2. These particles or ions could be transformed into ferrous ion by oxidation at the electrode during solution plasma treatment as follows (Sarahney et al., 2012):

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200 Fe
$$\longrightarrow$$
 Fe²⁺ + 2e- (2)

As previously reported by Chang *et al.* (Chang et al., 2011), the ferrous ion could enhance the Fenton reaction which decomposes the H₂O₂ generated in the system during solution plasma treatment and provided high amounts of hydroxyl radicals as follows:

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$$Fe^{2+} + H_2O_2 \longrightarrow Fe^{3+} + OH^{\bullet} + OH^{-}$$
 (3)

208
$$Fe^{3+} + O_2^{-}$$
 \longrightarrow $Fe^{2+} + O_2$ (4)

Therefore, the decomposition of H_2O_2 by Fenton reaction may also be responsible for a decrease in the molecular weight of degraded products. Moreover, the generated iron particles could react with chitosan to form the chitosan-metal complex by the interaction of OH and NH_2 groups on the chitosan structure. This led to an enhanced degradation of chitosan, since the polymeric chitosan chain in the chitosan-metal complex was broken down more easily than that of chitosan itself (Pornsunthorntawee et al., 2014).

Considering the effects of pulse frequency on molecular weight reduction, as shown in Table 1, it was observed that the molecular weight of the degraded product decreased with increasing pulse frequency. The molecular weight of chitosan after plasma treatment at the applied pulse frequencies of 15 kHz, 22.5 kHz, and 30 kHz were measured to be 1.3×10^4 Da, 9.2×10^3 Da, and 6.8×10^3 Da, respectively. The greater improvement in the molecular weight reduction at high pulse frequency could be attributed to the energy input increased when the pulse frequency increased, as previously reported by Kang *et al.* (Kang et al., 2013). The increase in energy input

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could enhance the amount of hydroxyl radical during solution plasma treatment. This could promote the degradation process of chitosan caused by plasma treatment, resulting in a high rate constant of the degradation reaction.

According to the results of molecular weight reduction, the degradation kinetics was then analyzed based on the relationship between the apparent molecular weight (M_w) of the chitosan sample and the reaction time as follows (Pornsunthorntawee et al., 2014):

$$\frac{1}{M_t} = \frac{1}{M_0} + \frac{kt}{M} = \frac{1}{M_0} + \hat{k}t$$
(5)

where M_t is M_w of chitosan sample at reaction time (t), M_θ is the initial M_w of the chitosan sample, M is the molecular weight of the chitosan monomer, k (min⁻¹) or k (gmol⁻¹. min⁻¹) is the degradation rate constant, and t is the reaction time. Figure 3 shows a linear relationship between the chitosan molecular weight and reaction time for the degradation of chitosan by solution plasma (reaction time between 0 min to 210 min). The k value of the degradation of chitosan by solution plasma using the W electrode was determined to be 3.77×10^{-2} min⁻¹. After Cu and Fe electrodes were introduced, the k values of degradation of chitosan were calculated to be 5.66×10^{-2} min⁻¹ and 1.22×10^{-1} min⁻¹, respectively. The obtained k value for the solution plasma treatment using Cu and Fe were higher than for the W electrode. Our results are consistent with those reported by Pornsunthorntawee et al., who studied depolymerization of the chitosan-metal complex via solution plasma. They suggested that the addition of Cu²⁺ and Fe²⁺ ions into chitosan solution could strongly promote the degradation rate of chitosan (Pornsunthorntawee et al., 2014). Considering the effect of pulse frequency on degradation rate, it was found that the k value of chitosan

effect of pulse frequency on degradation rate, it was found that the k value of chitosan

degradation was increased with increasing pulse frequency. The k values of chitosan degradation treated by solution plasma at pulse frequency of 22.5 kHz and 30 kHz were calculated to be 1.77x10⁻¹ min⁻¹ and 2.39x10⁻¹ min⁻¹, respectively. Based on the calculation of k, the order of degradation reaction of chitosan by solution plasma was evaluated to be Fe at 30 kHz $(2.39 \times 10^{-1} \, \text{min}^{-1}) \sim \text{Fe}$ at 22.5 kHz $(1.77 \times 10^{-1} \, \text{min}^{-1}) > \text{Fe}$ at 15 kHz $(1.22 \times 10^{-1} \text{ min}^{-1})$ > Cu at 15 kHz $(5.66 \times 10^{-2} \text{ min}^{-1})$ >> W at 15 kHz (3.77x10⁻² min⁻¹). Therefore, our results clarified that the solution plasma treatment using Fe electrode at high pulse frequency is an effective condition for degradation of chitosan. Moreover, the calculated k of the chitosan degradation by the solution plasma treatment using Fe electrodes was much higher than those previously reported in the literature. For example, the k value of the enzymatic degradation of chitosan and chitosan degradation in the presence of H2O2 was reported to be in the range of 10^{-5} – 10^{-4} min⁻¹ (Chang et al., 2001; Ilyina et al., 2000). This was approximately 2–3 orders of magnitude lower than our results.

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3.3 XRD analysis

The X-ray diffraction patterns of plasma-treated and untreated chitosan are shown in Figure 4. It was observed that the untreated chitosan sample displayed a crystal structure with two characteristic peaks at $2\theta = 15.1^{\circ}$ and 21.4° , which is referred to as the mixture of the "tendon hydrate polymorph" and "annealed polymorph" (Ogawa, 1991). After plasma treatment using the W electrode for 210 minutes, the diffraction peak located at a 2θ of 15.1° disappeared while the peak located at a 2θ of 21.4° became broader. This suggested that the crystalline region of the chitosan sample was destroyed during plasma treatment. When the Cu electrode was applied, the diffraction peak at 2θ equal to 15.1° in the XRD patterns of the

degraded chitosan products still disappeared but the peak at a 2θ of 20° was much broader with a much lower peak intensity. Interestingly, it was observed that after the chitosan was treated with plasma using the Fe electrode at the pulse frequency of 15 kHz and 30 kHz, the diffraction peak located at a 2θ of 15.1° and 21.4° disappeared. These results revealed that the solution plasma treatment of chitosan using Fe electrodes could disrupt the crystalline structure of the chitosan sample more than W and Cu electrodes. This corresponds to the results regarding the degradation rate of chitosan, as shown in Figure 3. An increase in disruption of the crystal structure of chitosan could improve an accessibility of hydroxyl radicals generated by plasma treatment, which enhanced the degradation process, and finally resulted in an increased degradation rate of chitosan.

3.4 FT-IR spectra

The FT-IR spectra of plasma-treated and untreated chitosan samples are shown in Figure 5. It was demonstrated that the characteristic peaks of untreated chitosan films appeared at 1668, 1558 and 1152 cm⁻¹, which corresponded to C=O stretching, -NH₂ bending, and -C-O-C- glycosidic linkage between chitosan monomer, respectively (Pornsunthorntawee et al., 2014; Li et al., 2012). After being treated with solution plasma, no additional characteristic peak was observed in the FTIR spectra of the degraded products. The characteristic peaks of plasma-treated chitosan mostly exhibited the same bands as the untreated sample. This indicated that the main polysaccharide structure of degraded chitosan remains unchanged. The degradation of chitosan by solution plasma treatment did not modify the chemical structure of chitosan. However, some differences between the chitosan products treated by solution plasma using Fe electrodes at both pulse frequency of 15 kHz and 30 kHz

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and untreated chitosan samples were observed in the range of 1300-1600 cm⁻¹. The bands at 1410 cm⁻¹ (symmetrical deformation of CH₃ and CH₂) and 1370 cm⁻¹ (bending and stretching of CH₃ and CH₂) were weakened. This implied that the intermolecular hydrogen bonding of plasma-treated chitosan was decreased. Moreover, its crystallinity was reduced during plasma treatment (Li et al., 2005).

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3.5 Fractionation of chitosan samples

Figure 6 shows the %vield of water-soluble and water-insoluble, as well as the total %yield, of chitosan samples as a function of type electrode and applied pulse frequency. The %yield of water-soluble chitosan (second precipitate) of the chitosan product after plasma treatment using W and Cu electrodes were measured to be 26% and 30%, respectively. When the Fe electrode was applied, the %yield of watersoluble chitosan increased greatly up to 60%. This result is also consistent with the calculated rate constant of the degradation reaction of the chitosan sample. This revealed that the solution plasma treatment of chitosan using Fe electrodes could induce the degradation of chitosan to obtain the highest amount of water-soluble chitosan products. However, some water-insoluble chitosan samples appeared in the degraded product. This might be a result of the non-uniformity and non-specific cleavage of degradation processes of chitosan by solution plasma treatment. Considering the effect of pulse frequency on chitosan products, it was found that the %vield of water-soluble chitosan products did not change when the pulse frequency was increased. This suggested that an increase in pulse frequency had an effect on the degradation rate but not the degraded chitosan product, i.e. the amount of water-soluble chitosan.

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4. Conclusion

In this study, a solution plasma system was introduced to treat β-chitosan solutions. The apparent molecular weight of plasma-treated chitosan solutions was decreased with increasing plasma treatment time, compared to that of an untreated sample. The degradation rate was greatly affected by the types of electrodes and the applied pulse frequency. The plasma treatment of chitosan using Fe electrode and high pulse frequency strongly promoted the degradation rate of chitosan. The degradation process of chitosan caused by plasma treatment has an effect on the molecular weight and crystal structure but not chemical structure of chitosan. We also found that solution plasma treatment of chitosan using Fe electrodes provided the highest %yield of water-soluble chitosan products compared to those W and Cu electrodes. These results implied that the Fe was suitable electrode for degradation of chitosan by solution plasma treatment.

Acknowledgements

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Figure captions

- Figure 1. Schematic diagram of solution plasma process.
- Figure 2. OES spectrum of plasma-treated chitosan solution (chitosan concentration and treatment time of 0.5% w/v and 1 min, respectively).
- Figure 3. Linear relationship between the inverse of the molecular weight (1/Mt) and the degradation time (t) for the degradation of the chitosan by solution plasma.
- Figure 4. X-ray diffraction patterns of plasma-treated and untreated chitosan.
- Figure 5. FT-IR spectra of plasma-treated untreated and chitosan films.
- Figure 6. %yield of water-insoluble chitosan, water-soluble chitosan, and total yield of degraded products obtained from solution plasma of chitosan.

Table caption

Table 1. Weight average molecular weight (Mw) and polydispersity index (PDI) of a chitosan sample after degradation by solution plasma process in a 0.5% (w/v) acetic acid solution using various types of electrodes and applied pulse frequency at 15-30 kHz.

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Table 1. Prasertsung, et al.

Reaction Time (min)	Molecular weight (Da)/(PDI)							
	Types of electrodes (Applied pulse frequency)							
	W (15 kHz)	Cu (15 kHz)	Fe (15 kHz)	Fe (22.5 kHz)	Fe (30 kHz)			
0	$1.3 \times 10^{5a} (3.5)^{b}$	1.3x10 ⁵ (3.5)	1.3x10 ⁵ (3.5)	1.3x10 ⁵ (3.5)	$1.3 \times 10^5 (3.5)$			
60	8.7x10 ⁴ (2.9)	$6.2x10^4$ (3.0)	$4.1x10^4$ (2.8)	$3.0 \times 10^4 (3.5)$	$2.6 \times 10^4 (3.5)$			
120	$6.4x10^4$ (2.9)	$4.3 \times 10^4 (2.8)$	$2.0x10^4$ (2.5)	$1.5 \times 10^4 (3.2)$	$1.2 \times 10^4 (3.0)$			
210	$3.1 \times 10^4 (2.7)$	$2.4 \times 10^4 (2.5)$	$1.3 \times 10^4 (2.3)$	$9.2 \times 10^3 (2.8)$	$6.8 \times 10^3 (2.7)$			

Reported values are M_w of the chitosan sample.

Reported values are the PDI of the chitosan sample.

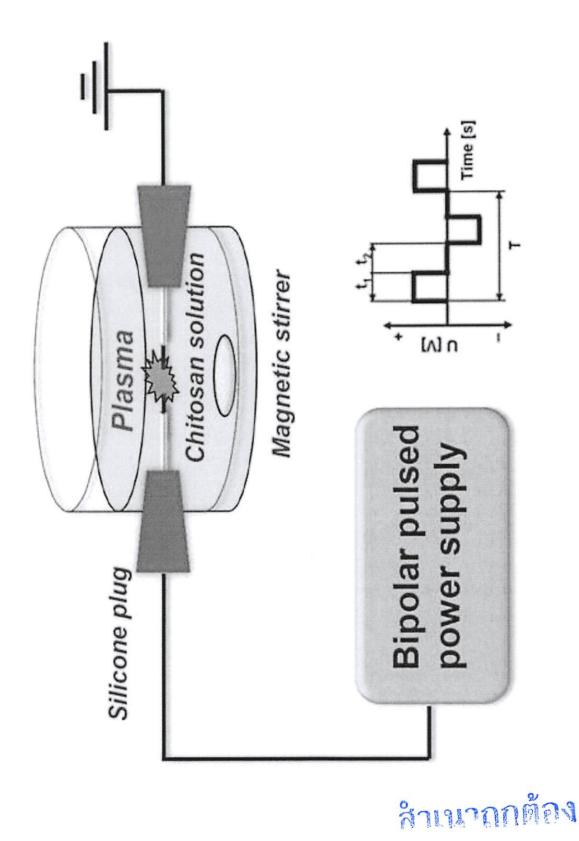
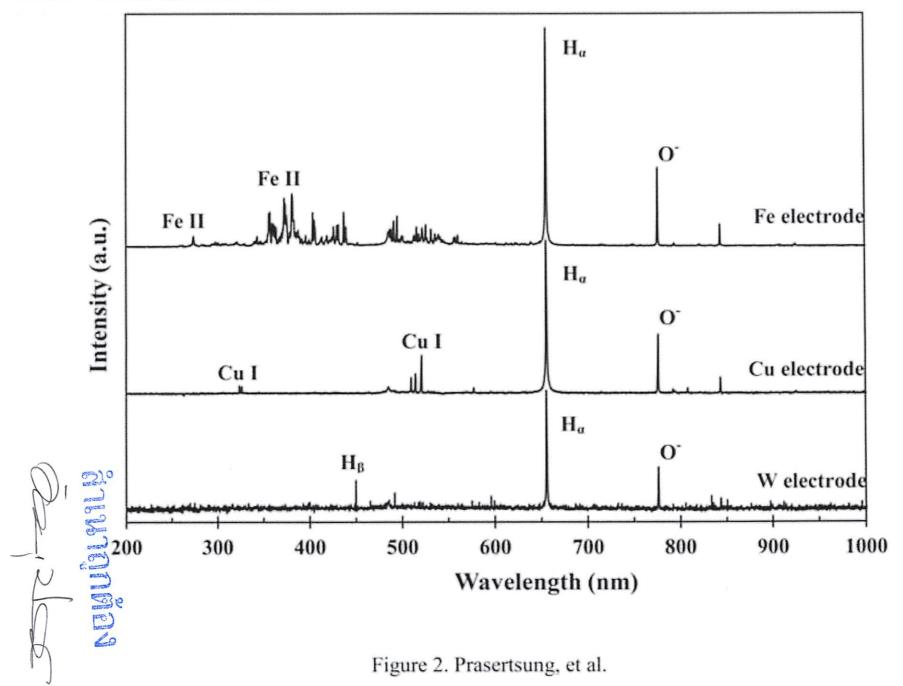


Figure 1. Prasertsung, et al.



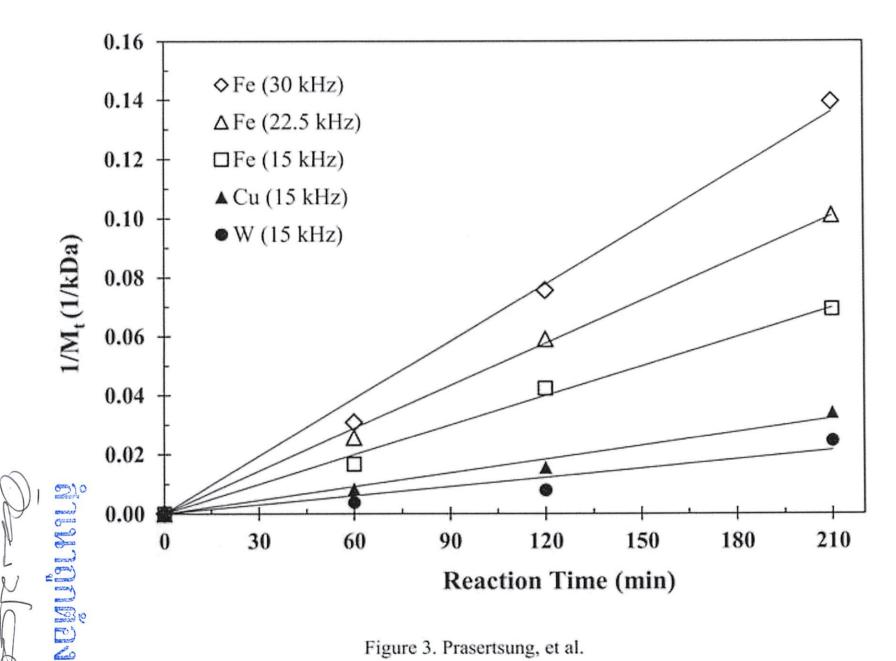


Figure 3. Prasertsung, et al.

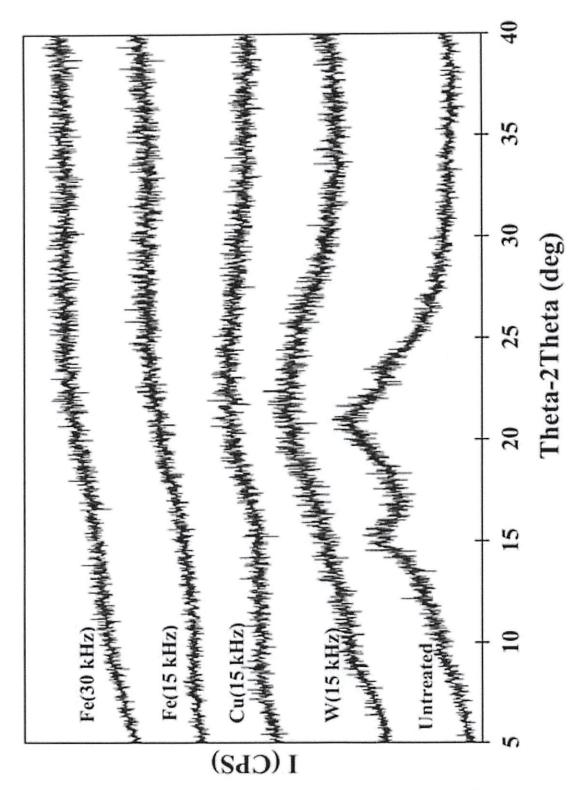


Figure 4. Prasertsung, et al.

กาเมาถูกห้อง

Figure5
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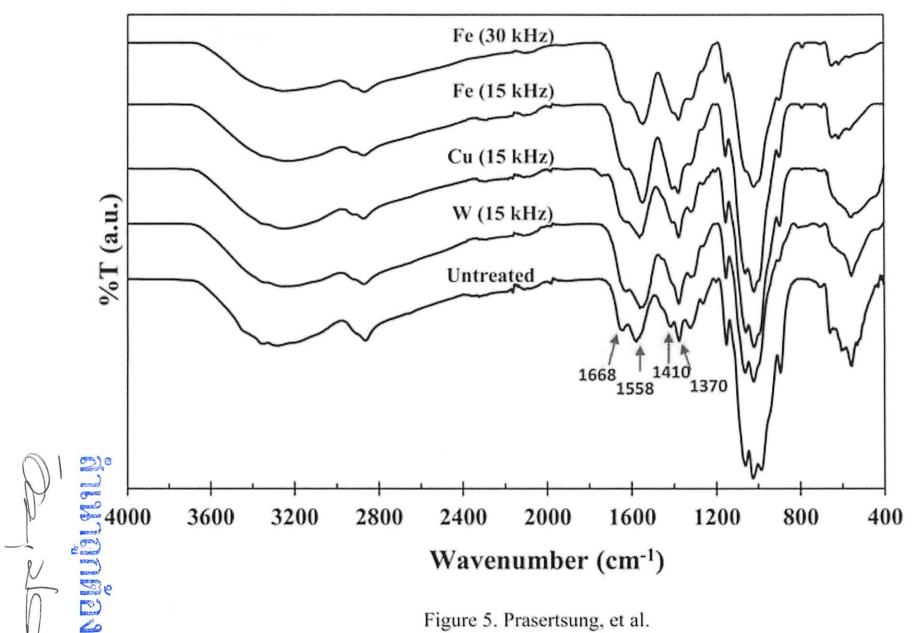


Figure6 Click here to download high resolution image

